



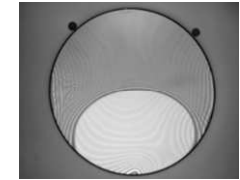
# DIRECT WAFER BONDING AT LETI

Leti Innovation Days | June 28-29, 2017

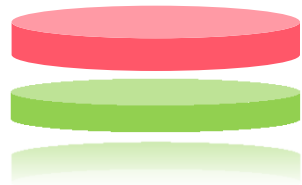
Frank Fournel  
Head of wafer bonding engineering



# DIRECT WAFER BONDING



*"spontaneous bonding at room temperature without polymer"*

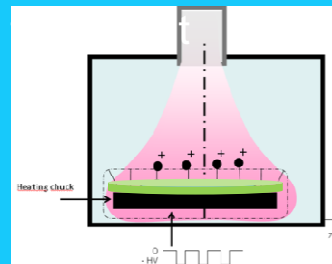


Wet cleaning

Ion beam surface activation



Plasma



## Surface preparations

- **Critical surface preparations**  
(roughness, flatness, defect level...)

- **Versatile** process
- **Mass production** demonstrated
- $\mu$ electronics and  $\mu$ technology processes **compatibility**
- Could be a **low temperature process**

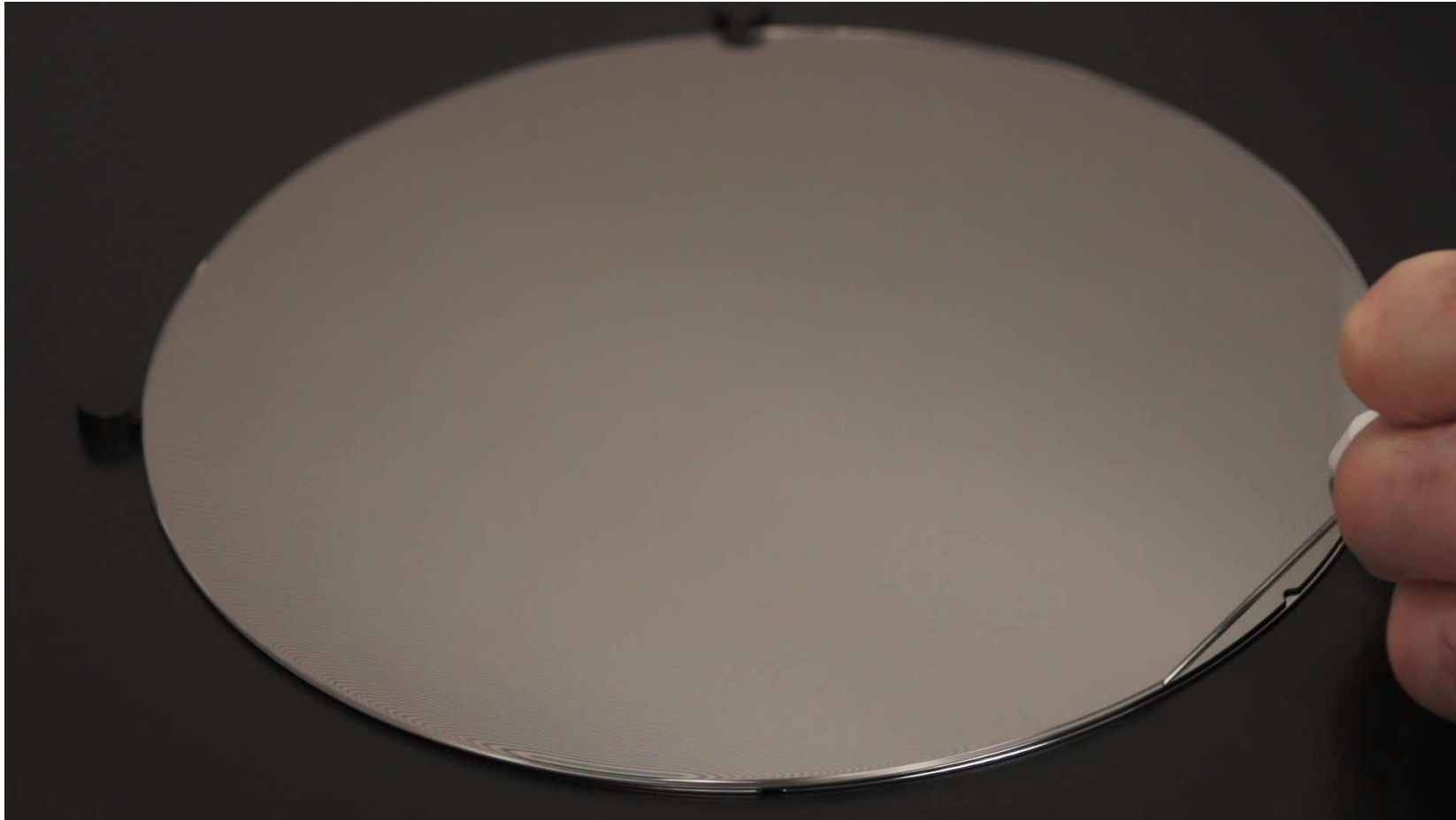
## Bonding





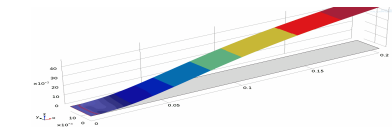
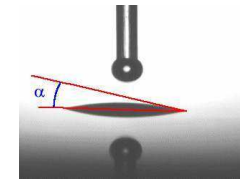
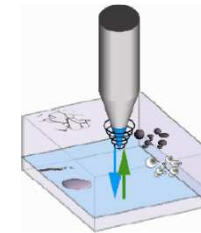
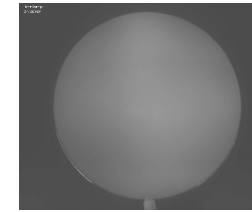
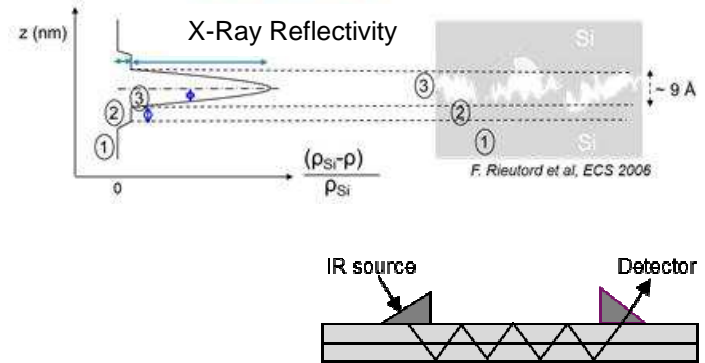
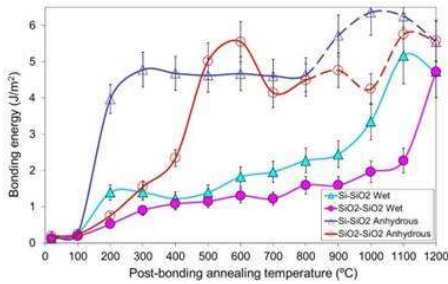
## DIRECT WAFER BONDING

*"spontaneous bonding at room temperature without polymer"*



# SILICON DIRECT WAFER BONDING

## Direct bonding studies



## Direct bonding mechanisms *(rough surface model with water management)*

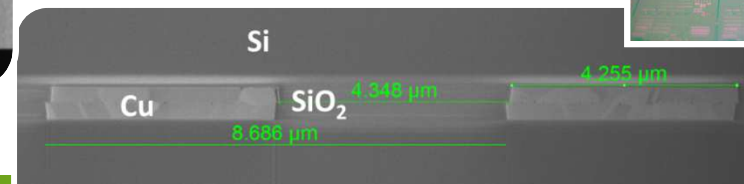
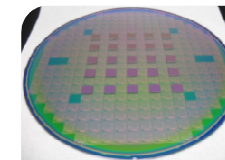
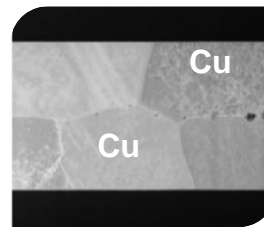
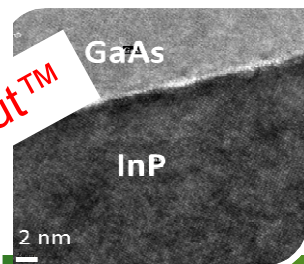


## Some realizations



soitec

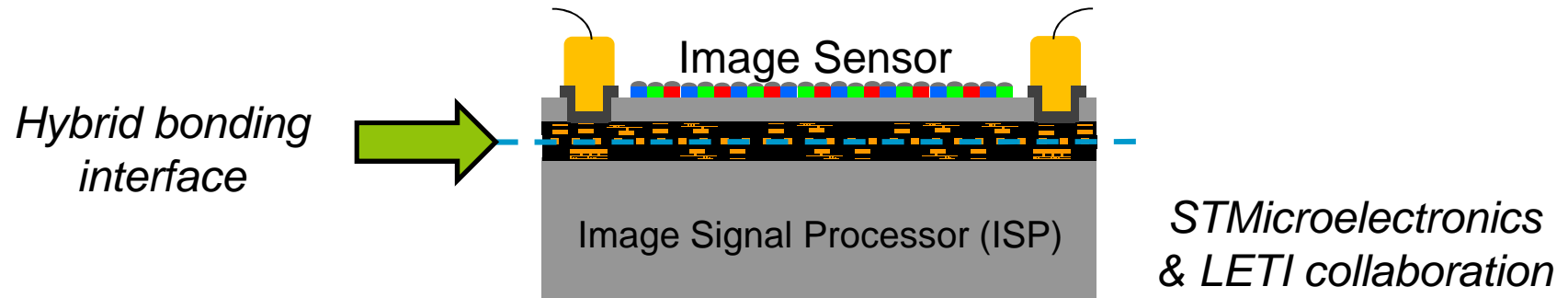
Smart Cut™



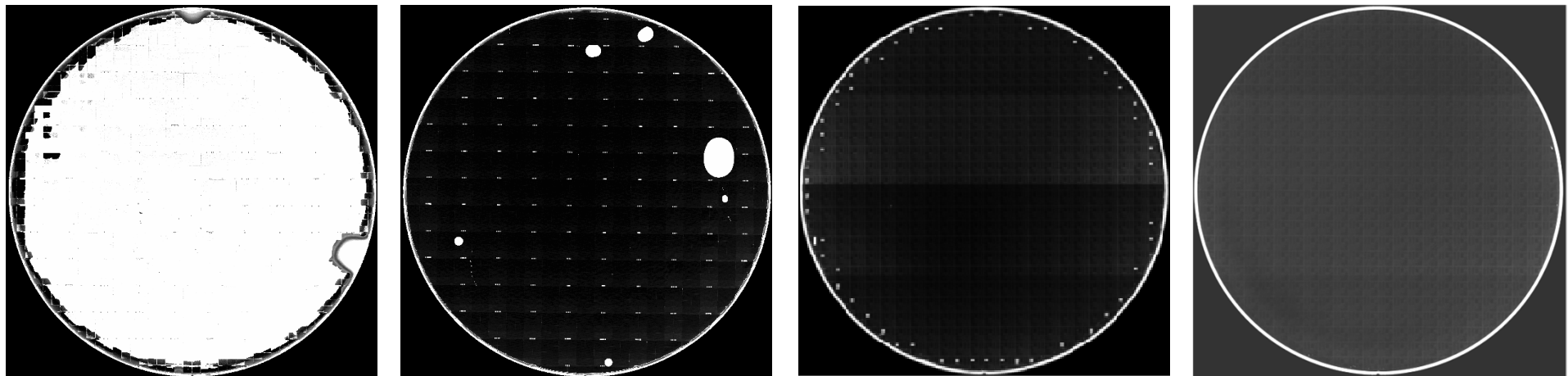


# HYBRID DIRECT WAFER BONDING

## New 3D imager sensor development with W2W hybrid bonding



### Direct hybrid bonding of BEOLs levels

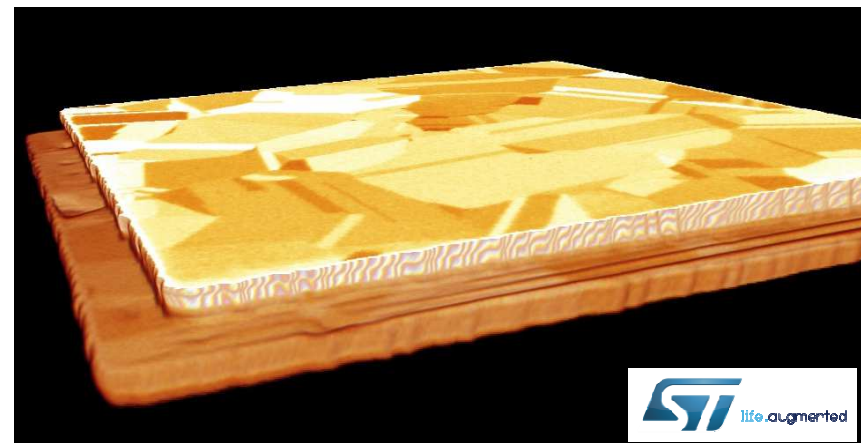
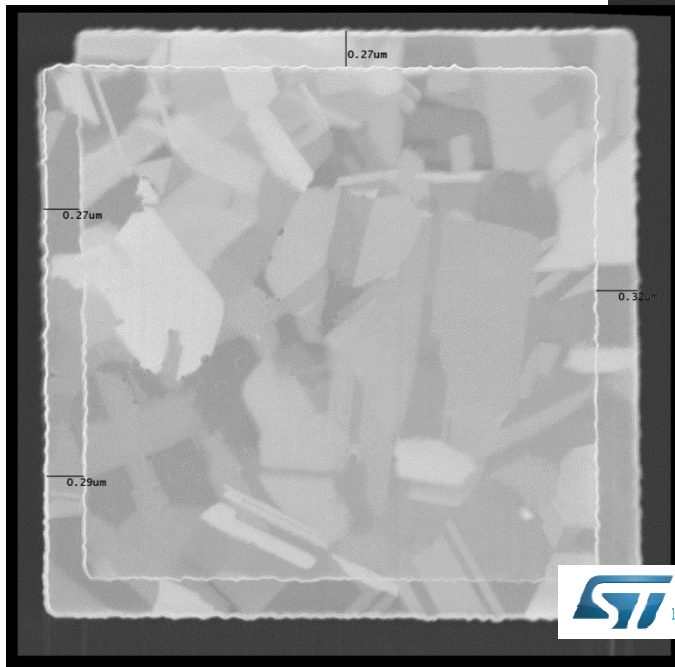
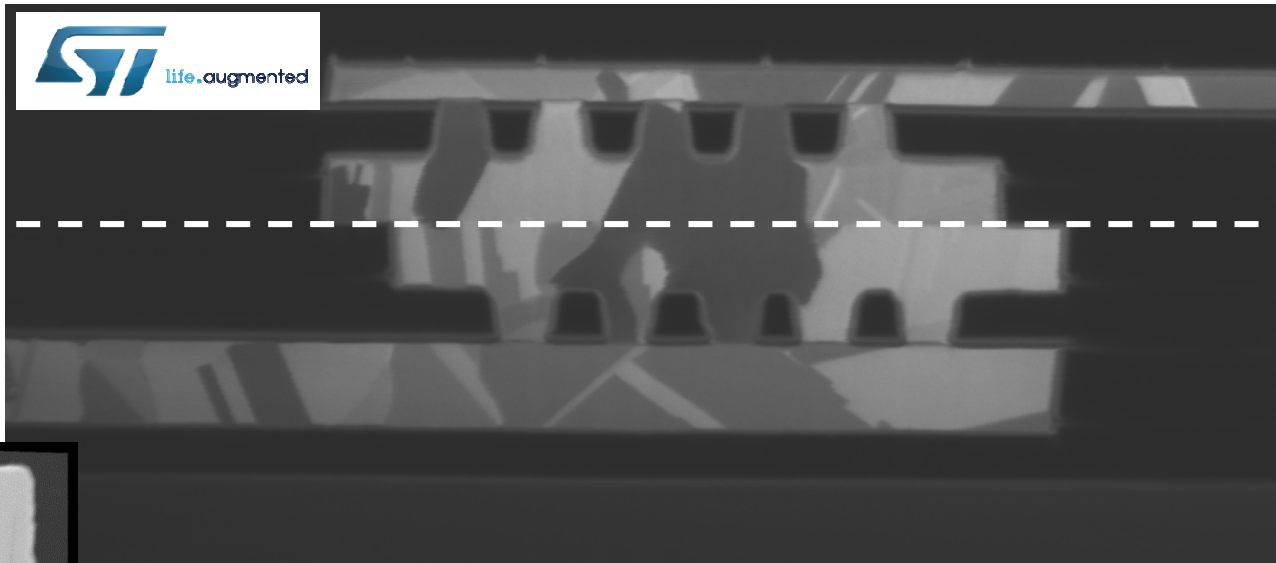




# HYBRID DIRECT WAFER BONDING

## Hybrid bonding

Typical Cu/Cu bonding pad with Cu crystal growth during bonding interface disappearance.



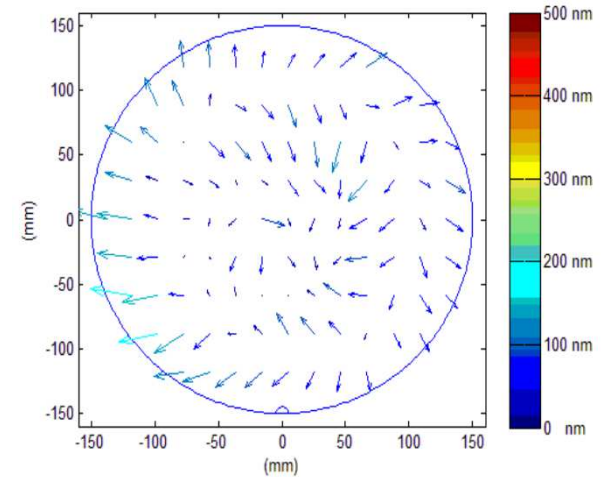


# HYBRID DIRECT WAFER BONDING

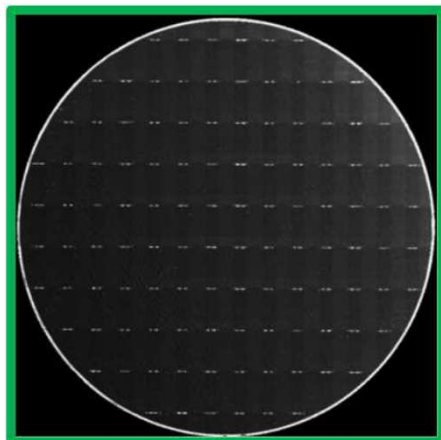
## Fine pitch



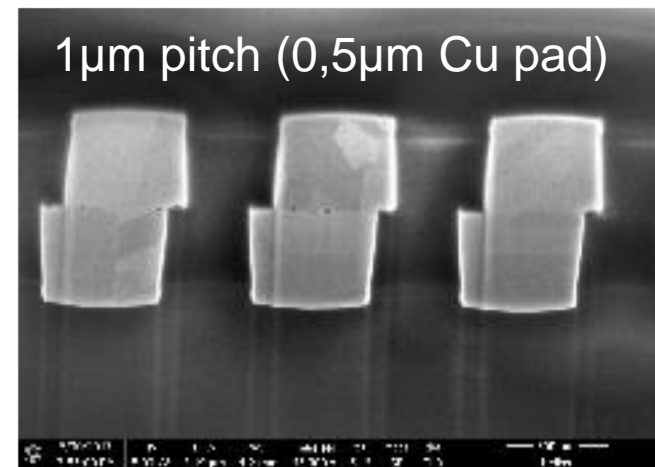
EVG Gemini



Global alignment : 10nm @ 3 $\sigma$  195 nm



Post-bonding SAM characterization



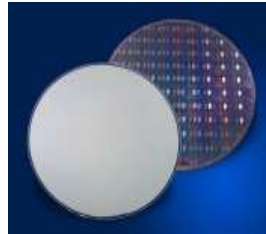
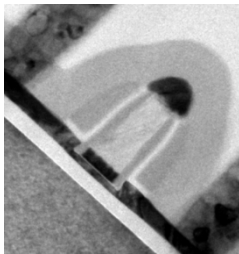


# DIRECT WAFER BONDING FOR MOORE LAW

SOI Substrates  
Mobility booster (sSOI, GeOI, ...)  
Ultrathin Buried Oxide  
Alternatives Buried Oxide (SiNx, C\*, ...)



soitec

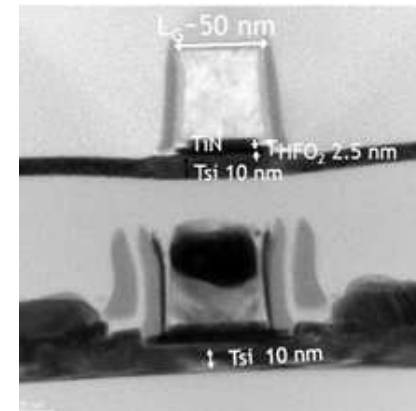
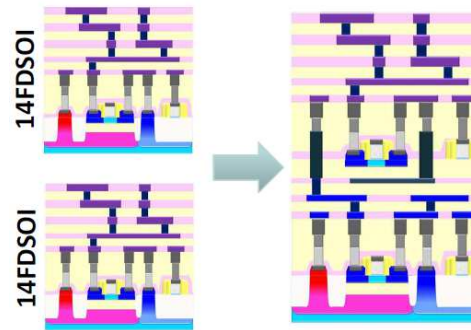


Alternative to Scaling

Monolithic 3D for further density scaling



Advanced substrates

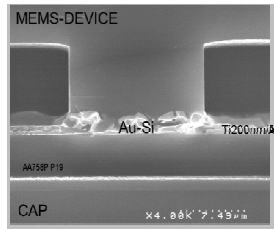


P. Batude, VLSI 2011





# AND ENABLING MORE THAN MOORE...



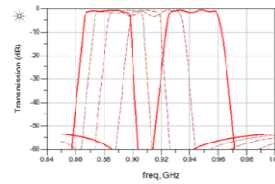
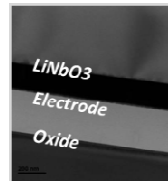
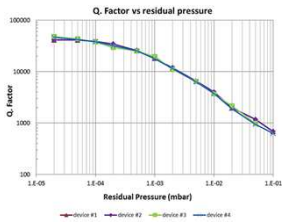
## Hermetic Wafer Level Packaging

S. Nicolas et al, ECTC 2011



Dutoit et al., VLSI Circuits 2013

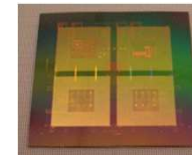
## Circuits on circuits Wide I/O Demonstrator



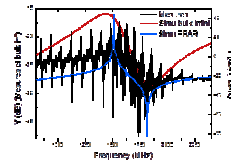
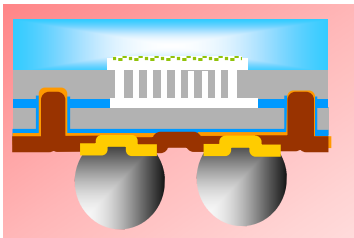
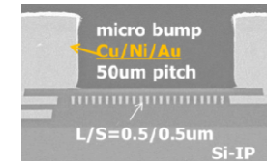
### 3D

## Applications

## High density 3D Silicon Interposer



J. Charbonnier et al., ESTC 2012, ECTC 2013



### RF



## High performances RF Filters

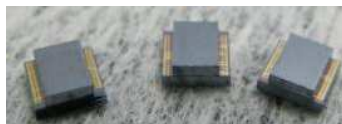
Piezoelectric thin film transfer

JS Moulet et al, IEDM 2008

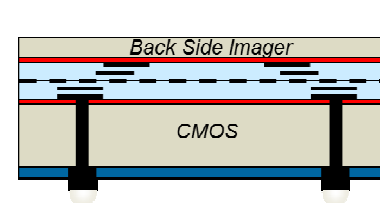
B. Imbert, IFCS 2011

Undisclosed industrial partner

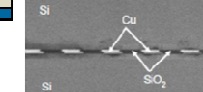
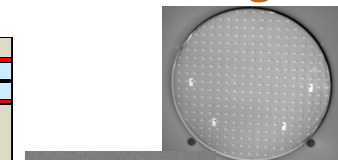
## MEMS



## 3D stacked CMOS imager



R Taibi et al, IEDM 2011





## CEA-LETI BONDING ECOSYSTEM

- Fundamental research through **academic collaborations**



- **R&D partnership with**

- Soitec (20 years long collaboration)
- EV Group (from 2013)
- ST microelectronics

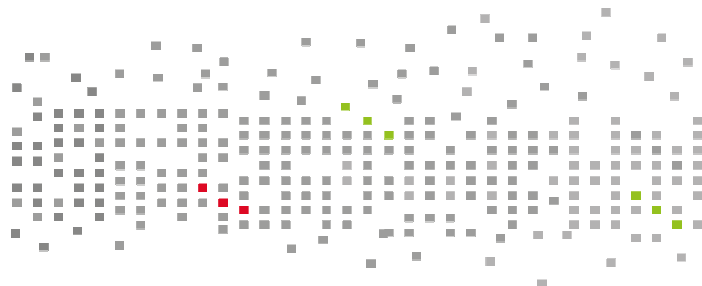


- Industrial **equipment suppliers** collaboration



- More than **60 patents** related to bonding tech. and app.
- **International recognition** with conference board
  - ECS (Wafer bond symposium), Wafer bond conference , EEE S3S conference ...

*Thank you !*



Leti, technology research institute

Commissariat à l'énergie atomique et aux énergies alternatives

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